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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/015,675	12/17/2001	Isao Ota	111483	5111
25944	7590 01/11/2006		EXAMINER	
OLIFF & BERRIDGE, PLC			UMEZ ERONINI, LYNETTE T	
P.O. BOX 19 ALEXANDR	928 IA, VA 22320		ART UNIT PAPER NUMBER 1765	
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DATE MAILED: 01/11/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)				
Office Action Summan	10/015,675	OTA ET AL.				
Office Action Summary	Examiner	Art Unit				
	Lynette T. Umez-Eronini	1765				
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address:	S			
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period was realized to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tiruly will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	N. nely filed the mailing date of this commun D (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 01 No	ovember 2005.					
<u> </u>	<u> </u>					
3) Since this application is in condition for allowar	nce except for formal matters, pro	secution as to the mer	its is			
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 4	53 O.G. 213.				
Disposition of Claims						
4)⊠ Claim(s) <u>1-3,10,12,13 and 16-18</u> is/are pending	g in the application.					
4a) Of the above claim(s) is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.						
6) Claim(s) <u>1-3,10,12,13 and 16-18</u> is/are rejected	d.					
7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/or	r election requirement.					
Application Papers						
9) The specification is objected to by the Examine	r.					
10) The drawing(s) filed on 11 July 2003 is/are: a)		by the Examiner.				
Applicant may not request that any objection to the		=				
Replacement drawing sheet(s) including the correcti	ion is required if the drawing(s) is ob	jected to. See 37 CFR 1.1	21(d).			
11)☐ The oath or declaration is objected to by the Ex	aminer. Note the attached Office	Action or form PTO-15	52.			
Priority under 35 U.S.C. § 119						
12)⊠ Acknowledgment is made of a claim for foreign	priority under 35 U.S.C. § 119(a))-(d) or (f).				
a)⊠ All b)□ Some * c)□ None of:						
1. Certified copies of the priority documents have been received.						
2. Certified copies of the priority documents have been received in Application No						
	3. Copies of the certified copies of the priority documents have been received in this National Stage					
application from the International Bureau	• • • • • • • • • • • • • • • • • • • •					
* See the attached detailed Office action for a list of	or the certilled copies not receive	;a.				
Attachment(s)						
Notice of References Cited (PTO-892)	4) Interview Summary	(PTO-413)				
2) D Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail Da	ate				
B) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date		atent Application (PTO-152)				
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DETAILED ACTION

Claim Rejections - 35 USC § 103

1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).
- 3. Claims 1-3 are rejected under 35 U.S.C. 103(a) as being unpatentable over Tastu et al. (US 4,769,073) in view of Ashley et al. (EP 444470 A1).

Tastu teaches an admixture that contains a cerium oxide and lanthanide salt and that has a pH of greater than 6 but not less than 10 (column 7, line 19 - column 8, line 7). The aforementioned reads on and encompasses,

A sol having a pH of 3 to 6 or 8 to 10, in claim 1.

Tastu also teaches an admixture with a solution of a cerium salt, an aqueous solution of a salt of at least one trivalent rare earth, which includes lanthanum,

praseodymium, and neodymium (column 4, lines 14-29) and lists a composition comprising: ceric oxide, lanthanum oxide, and neodymium oxide and having a mean particle diameter of 1.5 +/- 1 μm, in EXAMPLE 1 (column 12, lines 13-37). Tatsu discloses ceric oxide in the form of the composition described in French Pat. No. 2,549,846 and such compositions comprise a crystallographic phase of CeO₂ type . . . and corresponding to the formula Ln_{2-x}Ce_xSi₂O₇in which . . . x is greater than or equal to 0 and less than 2" (column 5, lines 7-15). The aforementioned further reads on,

A sol in which particles are dispersed in a medium, wherein the particles comprise as a main component crystalline cerium oxide of the cubic system and as an additional component a lanthanum compound, neodymium compound or a combination thereof and encompasses wherein the additional component is contained in X/(Ce + X) molar ratio of 0.005 to 15 in which X is lanthanum atoms, neodymium atoms or a combination thereof, in claim 1;

wherein the additional component is a lanthanum compound, in claim 2; and wherein the additional component is a neodymium compound, in claim 3;

Tastu differs in failing to teach a particle size of 2 to 200 m²/g, in claim 1.

Ashley discloses a stable ceria composition of one or more of La, Nd or Y and the stabilized ceria retains a surface area of greater than 20 m²/g (Abstract), which encompasses a particle size of 2 to 200m²/g.

Since Ashley illustrates the specific combination of particles having a surface area of 2 to 200 m²/g is known, then it would have been obvious to one having ordinary skill in the art at the time the invention was made to select any range of surface area as

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taught by Ashley, including applicants' specifically claimed range of surface area for the purpose of forming a high surface area ceria composition by incorporating one or more of La or Nd to the composition (Ashley, Abstract).

4. Claims 10 and 12, 13, and 15-18 are rejected under 35 U.S.C. 103(a) as being unpatentable over Tastu (US '073) in view of Ashley (US '470 A1) and further in view of Aozasa (US 6, 171,572 B1)

Tastu teaches an admixture that contains a cerium oxide and lanthanide salt and that has a pH of greater than 6 but not less than 10 (column 7, line 19 - column 8, line 7). The aforementioned reads on and encompasses,

an abrasive containing a sol having a pH of 3 to 6 or 8 to 10, in claim 10.

Tastu also teaches an admixture with a solution of a cerium salt, an aqueous solution of a salt of at least one trivalent rare earth, which includes lanthanum, praseodymium, and neodymium (column 4, lines 14-29) and lists a composition comprising: ceric oxide, lanthanum oxide, and neodymium oxide and having a mean particle diameter of 1.5 +/- 1 μm, in EXAMPLE 1 (column 12, lines 13-37). Tatsu discloses ceric oxide in the form of the composition described in French Pat. No. 2,549,846 and such compositions comprise a crystallographic phase of CeO₂ type . . . and corresponding to the formula Ln_{2-x}Ce_xSi₂O₇ in which . . . x is greater than or equal to 0 and less than 2" (column 5, lines 7-15). The aforementioned reads on,

an abrasive containing sol in which particles are dispersed in an aqueous medium, wherein the particles comprise as a main component crystalline cerium oxide

of the cubic system and as an additional component a lanthanum compound, neodymium compound or a combination thereof and encompasses wherein the additional component is contained in X/(Ce + X) molar ratio of 0.005 to 0.15 in which X is lanthanum atoms, neodymium atoms or a combination thereof, in claim 10;

wherein the additional component is a lanthanum compound, in claim 12; and wherein the additional component is a neodymium compound, in claim 13.

As pertaining to claims 16-18, since Tatsu uses the same composition as claimed by applicants, then using Tatsu's composition in the same manner as in the claimed invention would respectively result in,

an abrasive, which is used for polishing a substrate, which comprises silica as a main component,

an abrasive, which is used for polishing a rock crystal, a quartz glass for photomask, a semiconductor device or a hard disk made of glass; and

an abrasive, which is used in a step of polishing an organic film, a step of polishing Inter Layer Dielectric (ILD) or a step of shallow trench isolation, for polishing a semiconductor device.

Tastu differs in failing to teach a sol in which particles are dispersed in an aqueous medium in a range of 0.1 to 50-wt % and a particle size of 2 to 200 m²/g, in claim 10.

Ashley discloses a stable ceria composition of one or more of La, Nd or Y to the ceria in an amount of from 5 to 25 mole % of the ceria and the stabilized ceria retains a

surface area of greater than 20 m²/g (Abstract), which encompasses particles having a range of 0.1 to 50-wt % and particle size of 2 to 200m²/g.

Since Ashley illustrates the specific combination of particles having a surface area of 2 to 200 m²/g is known, then it would have been obvious to one having ordinary skill in the art at the time the invention was made to select any range of wt % and surface area as taught by Ashley, including applicants' specifically claimed range of wt % and surface area for the purpose of forming a high surface area ceria composition by incorporating one or more of La or Nd to the composition (Ashley, Abstract).

Tastu in view of Ashley differs in failing to teach a sol wherein the particles have a particle size of 50 to 150 nm, in claim 10.

Aozasa teaches, "... a cerium sol having an average colloidal particle size of 3 to 100 nm, and optionally one or more members selected from the group consisting of salts of yttrium, scandium, lanthanum, praseodymium, neodymium, samarium, europium, gadolinium, magnesium, calcium, barium, aluminum, titanium, and hafnium.
..." (column 3, lines 49) and "... a cerium sol having an average colloidal particle size of 3 to 100 nm, preferably 5 to 80 nm, more preferably 10 to 50 nm. . . . If the average colloidal particle size is smaller than 3 nm, production in industrial scale will be difficult" column 5, lines 52-59). Aozasa also teaches, cerium sol having a concentration of about 100 to 200 g/liter (~ 10 to 20 g/100 ml or 10-20 wt %), (column 6, lines 4-6).

It would have been obvious to one having ordinary skill in the art at the time of the claimed invention to modify the combination or abrasive materials as taught by Art Unit: 1765

Tastu in view of Ashley, by using Aozasa's sol having a particle size of 3 to 100 nm which falls within the particle size range as claimed by applicants for the purpose of ease of production on an industrial scale (Aozasa, column 8, lines 42-45).

Response to Arguments

5. Applicants' arguments with respect to claims 1-3, 10, 12, 13, and 16-18 have been considered but are moot in view of the new ground(s) of rejection because the formerly applied prior art fail to address, a sol having a --pH of 3 to 6 or 8 to 10-- and -- have a specific surface area of 2 to 100 m²/g--, . . ." as recited in (Currently Amended) Claims 1 and 10.

Conclusion

6. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of

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the advisory action. In no event, however, will the statutory period for reply expire later

than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Lynette T. Umez-Eronini whose telephone number is

571-272-1470. The examiner is normally unavailable on the First Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Nadine Norton can be reached on 571-272-1465.

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Business Center (EBC) at 866-217-9197 (toll-free).

Itue

January 4, 2006

NADINE G. NORTON SUPERVISORY PATENT EXAMINER

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